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LW  
2/21/03  
(NE)

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

RECEIVED  
FEB 20 2003  
TC 1700

IN RE APPLICATION OF :  
HIROYUKI YANO ET AL : EXAMINER: DEO, D. V.  
SERIAL NO: 09/531,163 :  
FILED: MARCH 17, 2000 : GROUP ART UNIT: 1765  
FOR: AQUEOUS DISPERSION, :  
AQUEOUS DISPERSION FOR  
CHEMICAL MECHANICAL  
POLISHING USED FOR  
MANUFACTURE OF  
SEMICONDUCTOR DEVICES,  
METHOD FOR MANUFACTURE OF  
SEMICONDUCTOR DEVICES, AND  
METHOD FOR FORMATION OF  
EMBEDDED WIRING

AMENDMENT AND REQUEST FOR RECONSIDERATION

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

SIR:

Responsive to the Office Action of November 15, 2002, Applicants respectfully  
request reconsideration of the above-identified application in view of the following  
amendment and remarks.

IN THE CLAIMS

Please cancel Claims 44-60.

Please add the following claims:

02/14/2003 NMOHAMM1 00000033 09531163

01 FC:1201

168.00 0P